

**LWIR HgCdTe - INNOVATIVE DETECTORS  
IN AN INCUMBENT TECHNOLOGY**

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**ABSTRACT**

HgCdTe is the current material of choice for high performance imagers operating at relatively high temperatures. Its lack of technological maturity compared with silicon and wide-band gap III-V compounds is more than offset by its outstanding IR sensitivity and by the relatively benign effect of its materials defects. This latter property has allowed non-equilibrium growth techniques (MOCVD and MBE) to produce device quality LWIR HgCdTe even on common substrates like GaAs and GaAs/Si. Detector performance in these exotic materials structures is comparable in many ways with devices in equilibrium-grown material. Lifetimes are similar. RoA values at 77K as high as several hundred have been seen in HgCdTe/GaAs/Si with 9.5  $\mu\text{m}$  cut-off wavelength. HgCdTe/GaAs layers with  $\sim 15 \mu\text{m}$  cut-off wavelengths have given average 77K RoAs of  $>2$ . Hybrid focal plane arrays have been evaluated with excellent operability.

# **LWIR HgCdTe - INNOVATIVE DETECTORS IN AN INCUMBENT TECHNOLOGY**

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## **OVERVIEW**

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**0 PACE BACKGROUND AND MATERIALS**

**0 TEST DIODE PERFORMANCE AND TECHNOLOGY LIMITS**

**0 PRELIMINARY LWIR ARRAY DATA**

**0 DIRECTIONS AND CONCLUSIONS**



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## DEFINITIONS

- CONVENTIONAL TECHNOLOGY

- MCT GROWN BY LIQUID PHASE EPITAXY ON CdTe OR SIMILAR COMPOUND

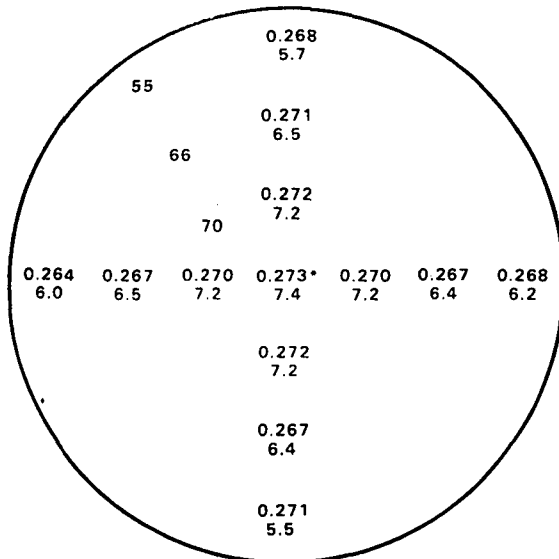
- PACE (PRODUCIBLE ALTERNATIVE TO CdTe FOR EPITAXY)

- ROCKWELL APPROACH TO OVERCOME MCT PRODUCIBILITY ISSUES

- **PACE-1:** MCT GROWN BY LIQUID PHASE EPITAXY ON VAPOR PHASE EPITAXIAL CdTe/SAPPHIRE -- SUITABLE FOR SWIR (1-3 MICRONS) AND MWIR (3-5+) MICRONS

- **PACE-2:** MCT GROWN BY VAPOR PHASE EPITAXY ON GaAs (OR EVENTUALLY Si) -- SUITABLE FOR ALL IR WAVELENGTHS

### PACE-2 HAS BETTER COMPOSITIONAL UNIFORMITY THAN LPE



3" DIA GaAs WAFER

$$\max \frac{\Delta x}{\bar{x}} = 3.3\%, \max \frac{\Delta \bar{d}}{\bar{d}} = 29\% \text{ OVER } 3'' \text{ DIA}$$

$$\max \frac{\Delta x}{\bar{x}} = 2.2\%, \max \frac{\Delta \bar{d}}{\bar{d}} = 17\% \text{ OVER } 2'' \text{ DIA}$$

**LEGEND**

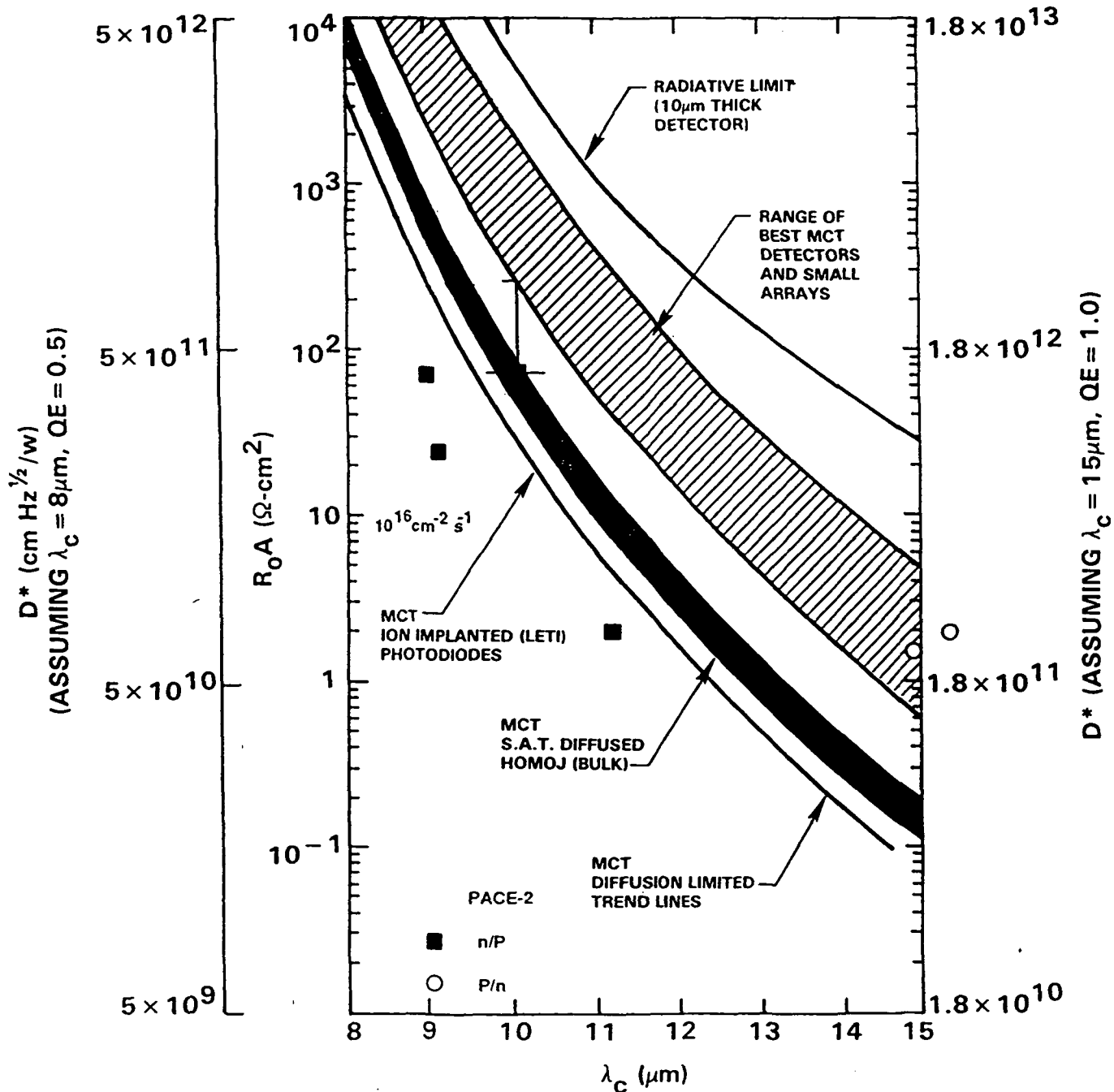
- \* — COMPOSITION, X VALUE
- THICKNESS,  $\mu\text{m}$
- CRYSTALLINITY, ARC-SEC



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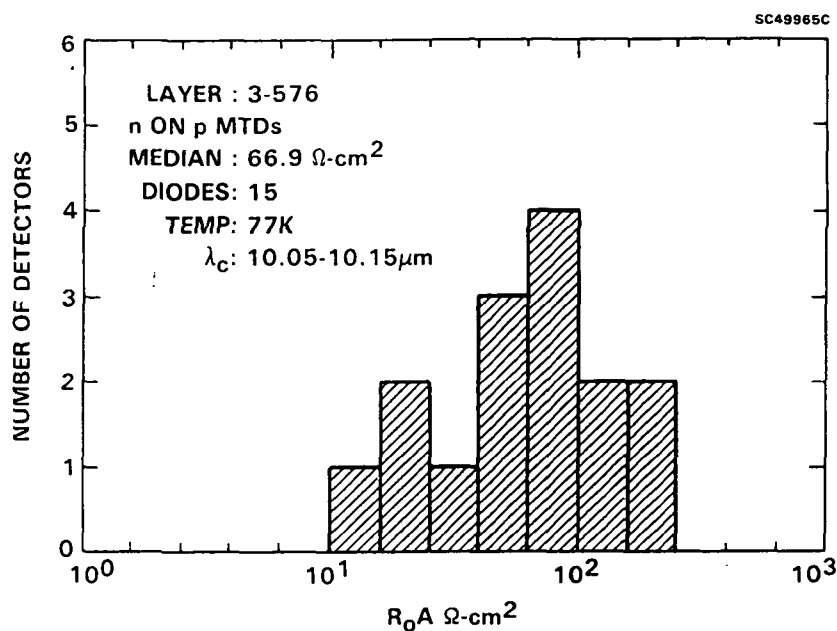
# LWIR TACTICAL MCT DETECTOR PERFORMANCE

SC50216

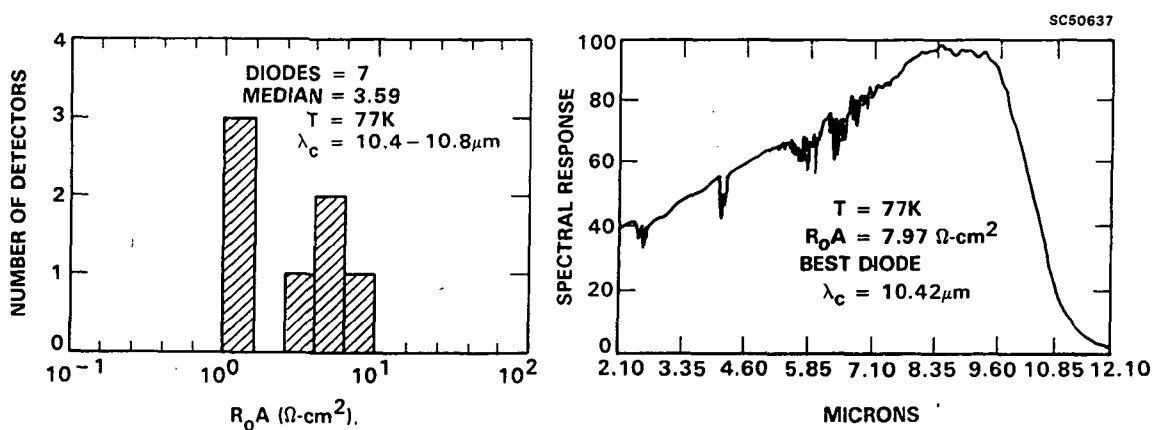


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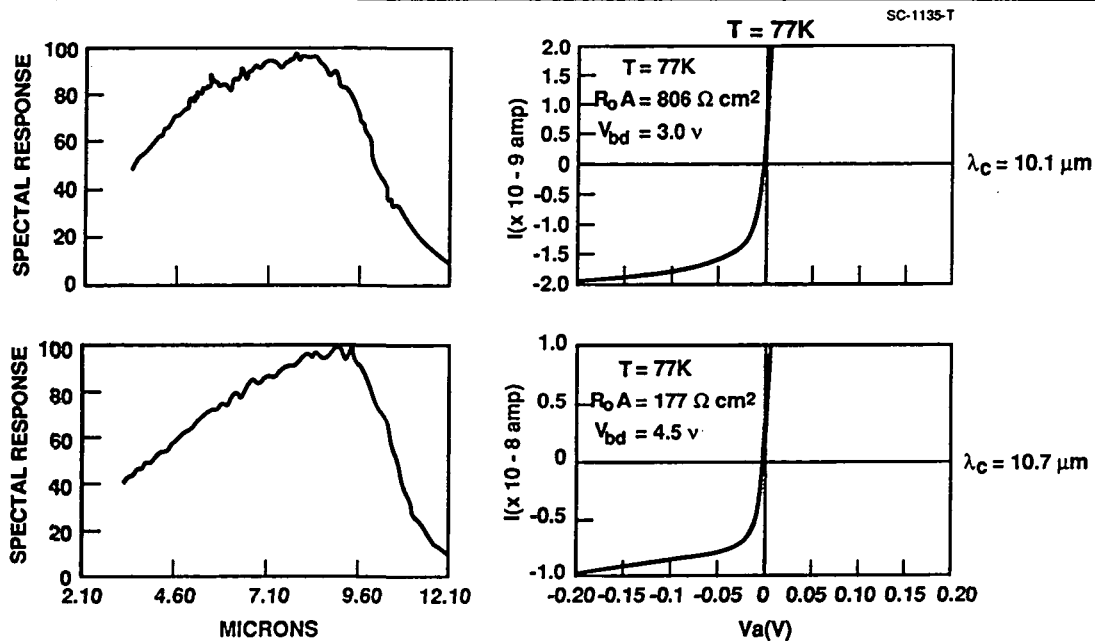
# $n^+ / p$ TEST DIODES IN HgCdTe/GaAs (PACE-2)



## MTD DATA FOR 3-623 BASELINE LAYER n ON p DEVICES, ION IMPLANTED



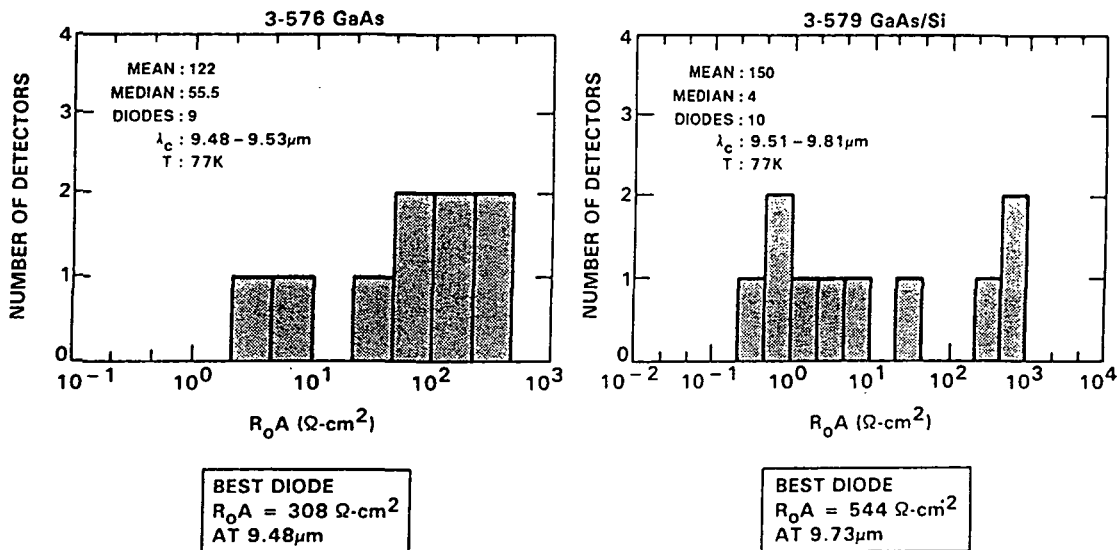
## LWIR HgCdTe/Pace-2 p/n Devices Show Higher Performance Than LPE Devices



- ARSENIC IMPLANATATION
- OMVPE HgCdTe ON GaAs

## RECENT p ON n MTD PERFORMANCE CONFIRM EARLIER RESULTS

### ARSENIC IMPLANT/DIFFUSION IN DOUBLE LAYER HETEROSTRUCTURE

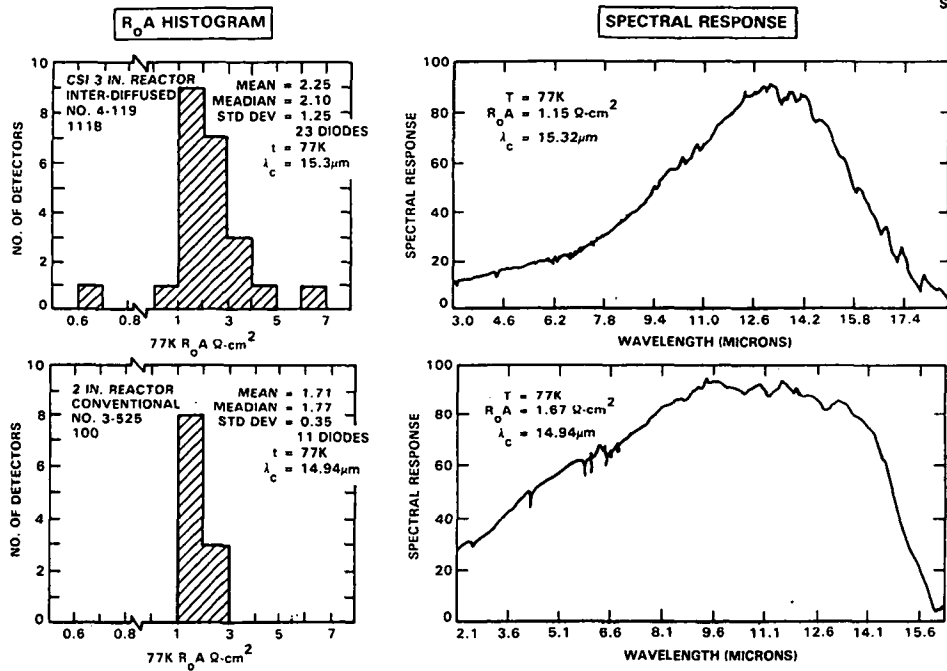


- n ON p DIODES HAVE BETTER UNIFORMITY



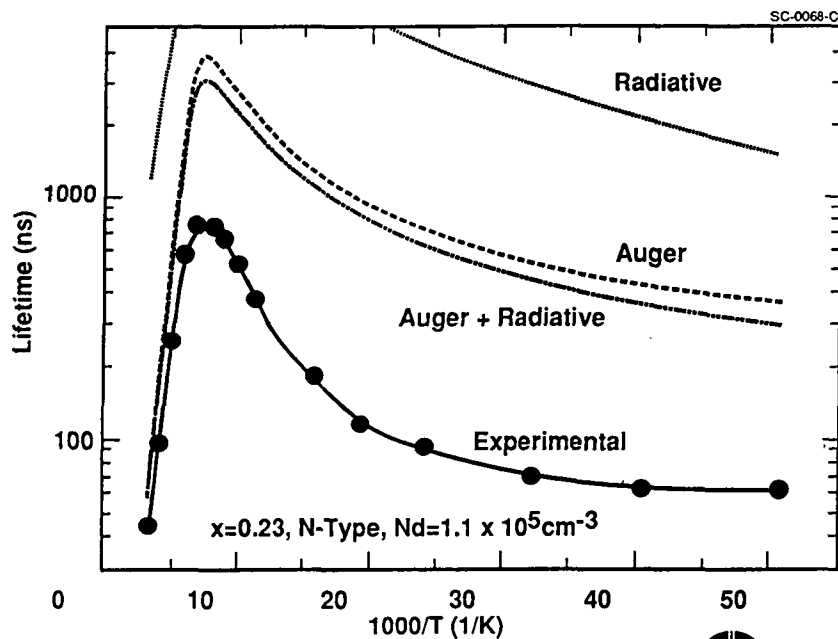
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# EXCELLENT DIODE PERFORMANCE IN VLWIR MOCVD MCT/GaAs p ON n DIODES

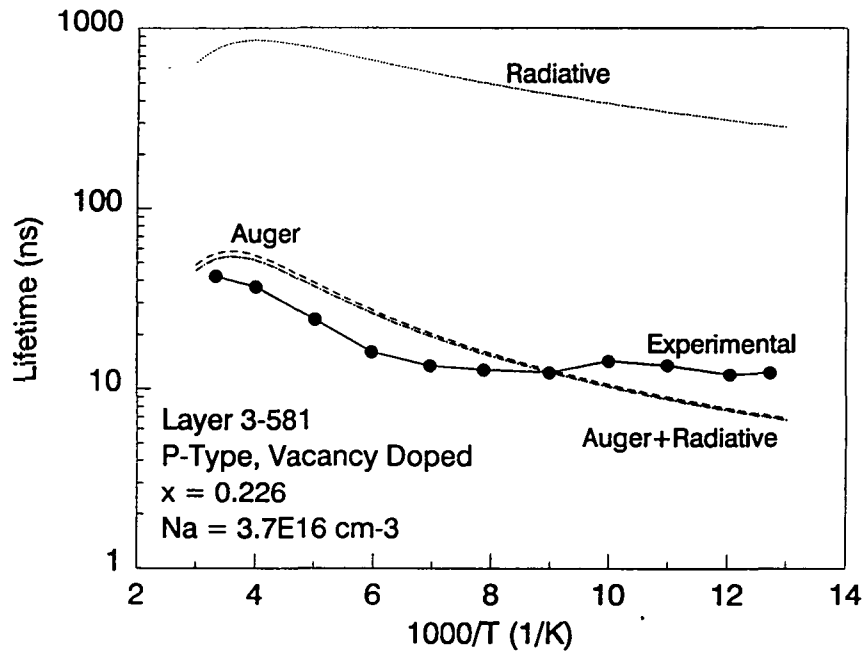


## Minority Carrier Lifetime

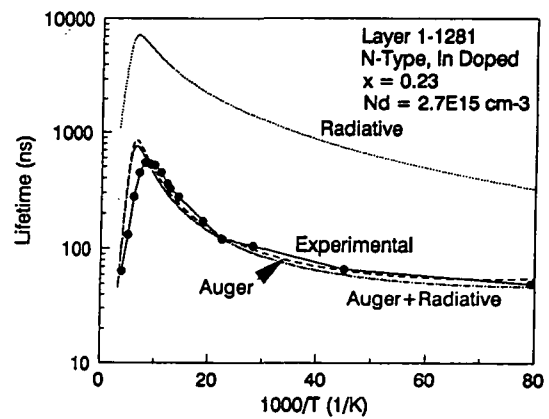
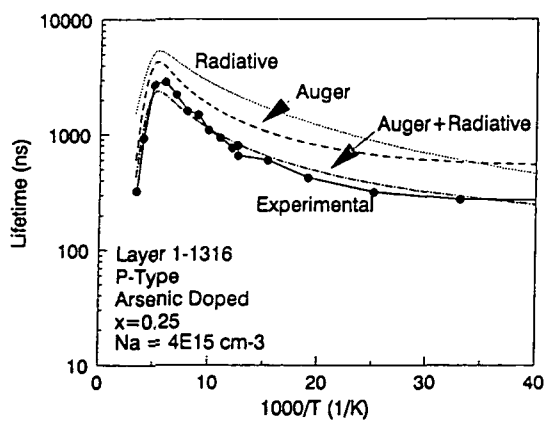
4-334, N-Type, Undoped,  $x=0.235$ ,  $N_d=1.1 \times 10^{15}\text{cm}^{-3}$



## LIFETIMES IN SOME VACANCY DOPED PACE-2 APPROXIMATE THEORY

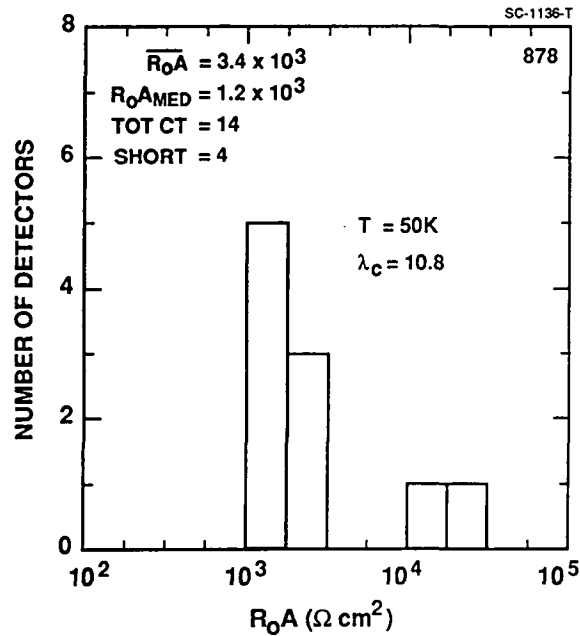


## BEST IMPURITY DOPED PACE-2 SAMPLES SHOW THEORETICAL LIFETIMES

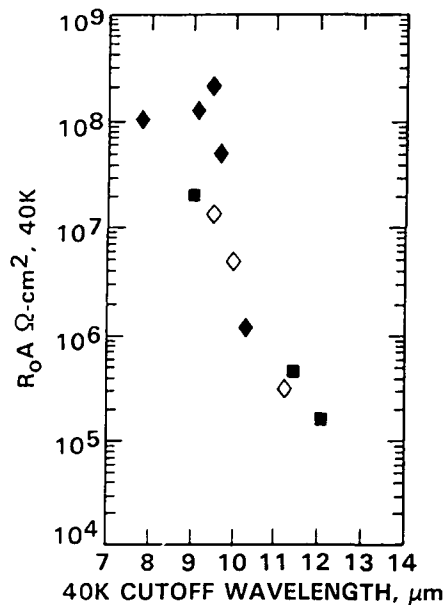




## Performance of an LWIR MCT/GaAs Array at 50K



## LWIR MOCVD HgCdTe/GaAs DIODES BEST PERFORMANCE IS AT TOP LPE LEVELS FOR 77 AND 40K

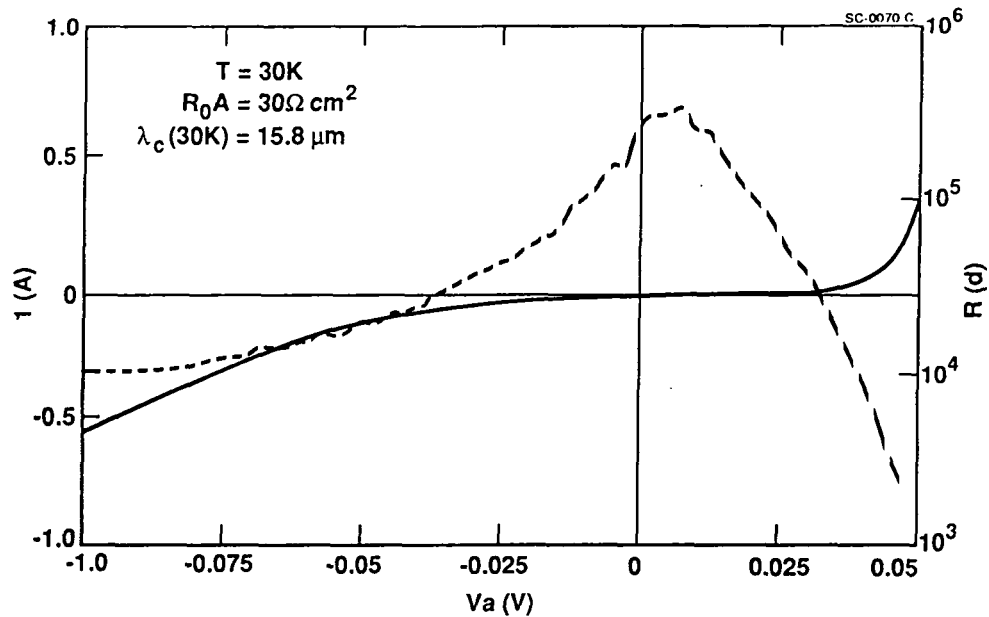


	P/N	N/P
LPE MCT/CdTe	◆	◇
MOCVD MCT/GaAs	■	



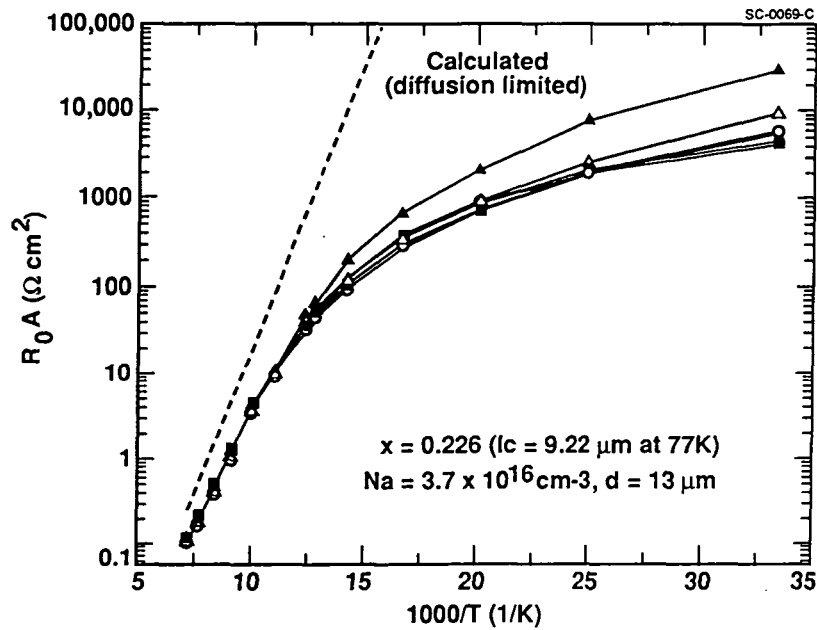
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## VLWIR I-V Characteristics for MOCVD Grown MCT/GaAs Detector



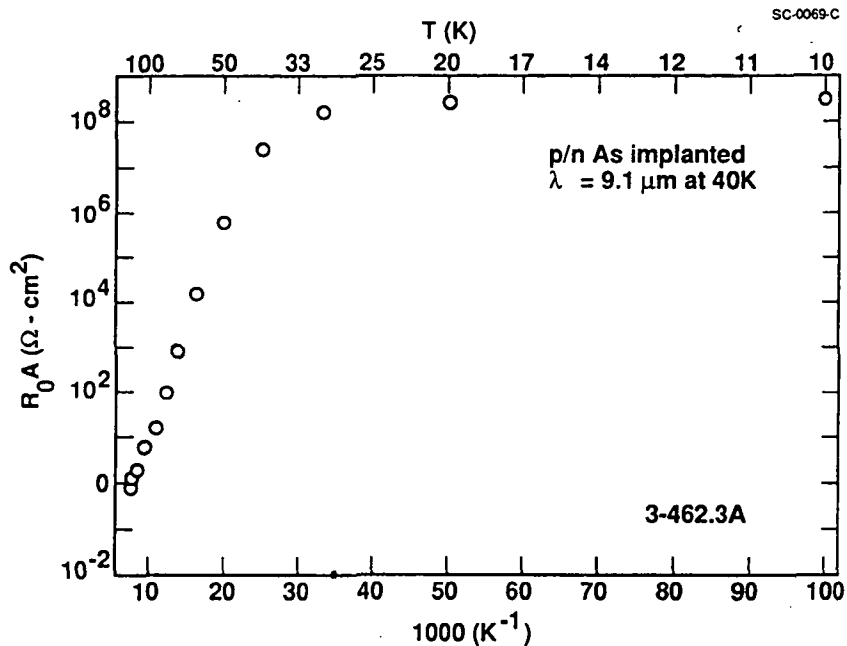
## $R_0A$ vs $1/T$

Layer 3-581, L-134, Planar Ion Implanted



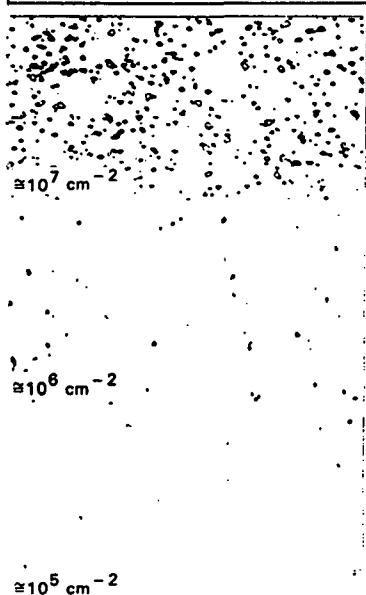
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# Temperature Dependence of the $R_0A$ Product of a P/N Diode Fabricated from PACE-2 Material



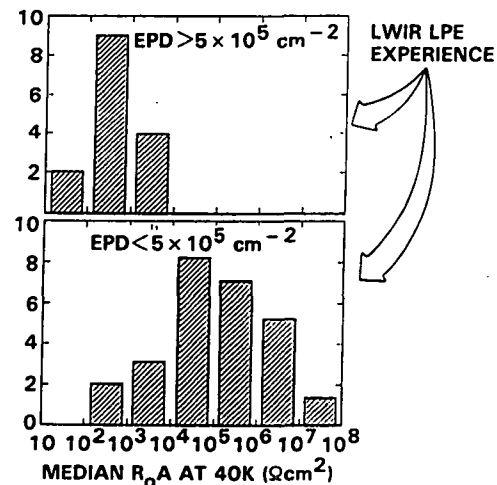
## STRATEGIC APPLICATIONS REQUIRE CONTROL OF DISLOCATION DENSITY

ETCH PIT DENSITY MCT/GaAs



LOW TEMPERATURE OPERATION IS MOST DEMANDING APPLICATION

SC49582



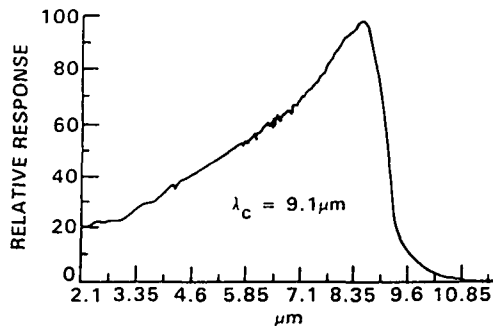
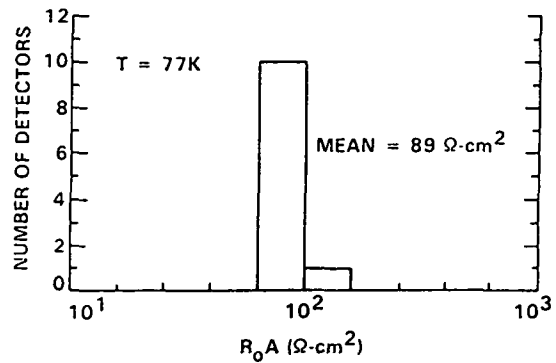
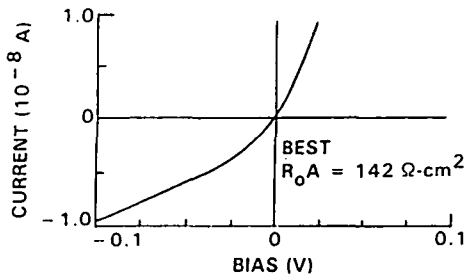
$\lambda_c \geq 9.1\text{-}10.3 \mu\text{m}$  AT 40K FOR 38 LAYERS



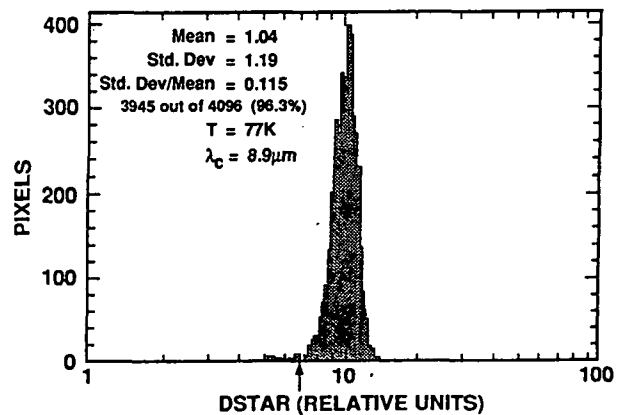
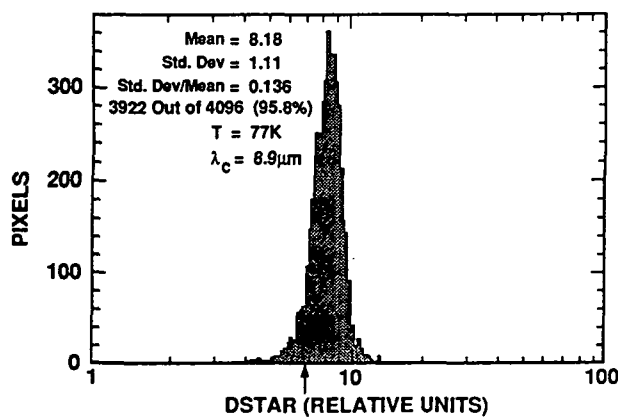
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# SAMPLE DIODES FROM PACE II 128 x 128 WAFER (ROCKWELL IR&D)

FULL PLANAR PROCESS: n/p, B-IMPLANTED, ZnS/SiO<sub>2</sub> PASSIVATED



## Pace-2 Shows D\* Uniformity and Operability of LWIR Hybrid



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## CONCLUSIONS

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- MCT HAS DEMONSTRATED THE HIGHEST PERFORMANCE OF ANY INTRINSIC AT ALL IR WAVELENGTHS
- NOVEL, ALTERNATIVE-SUBSTRATE, VPE APPROACHES CAN MEET PROGRAM GOALS WHILE ENHANCING PRODUCIBILITY AND MAKING POSSIBLE ADVANCED ARCHITECTURES
- THE PRESENT LIMITATIONS OF THE TECHNOLOGY ARE NOT FUNDAMENTAL BUT DUE TO IMMATURITY
- WE EXPECT LWIR/PACE-2 (GaAs) OR 3 (Si) TO FOLLOW A SIMILAR PATH TO PRODUCIBILITY AS THAT OF MWIR PACE-1 WHICH HAS RESULTED IN THE LARGEST (256X256) INTRINSIC IR FPA TO DATE



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